

Wet benches

RCA cleaning bench

- RCA chemicals used: DI water, NH_4OH , H_2O_2 , HCl , HF
- Piranha chemicals used: H_2SO_4 , H_2O_2
- HF cleaning: 2% HF
- Substrates used: Si, glass.
- Substrate size: Max 4" diameter wafer.



Silicon and metal etching bench

- Used for Si, poly silicon, nitride, metal etching
- Si etchant: TMAH, HNA
- SiO_2 etchants: 5:1 BHF and 7:1 BHF
- Silicon nitride: HNA
- Al etchant:
- Cr-Au etchant: CEN for Cr and $\text{KI} + \text{I}_2 + \text{Di water}$ for Au



